

Articles in reference type

Chang, S., Geng, Y. & Yan, Y. **Tip-Based Nanomachining on Thin Films: A Mini Review.** *Nanomanuf Metrol* 5, 2–22 (2022). <https://doi.org/10.1007/s41871-021-00115-5>

O'Neill, K., Greig, R., Tilmann, R. *et al.* **Patterning Functionalized Surfaces of 2D Materials by Nanoshaving.** *Nanomanuf Metrol* 5, 23–31 (2022).
<https://doi.org/10.1007/s41871-021-00122-6>

Han, W., Mathew, P.T., Kolagatla, S. *et al.* **Toward Single-Atomic-Layer Lithography on Highly Oriented Pyrolytic Graphite Surfaces Using AFM-Based Electrochemical Etching.** *Nanomanuf Metrol* 5, 32–38 (2022). <https://doi.org/10.1007/s41871-022-00127-9>

Fan, P., Goel, S., Luo, X. *et al.* **Atomic-Scale Friction Studies on Single-Crystal Gallium Arsenide Using Atomic Force Microscope and Molecular Dynamics Simulation.** *Nanomanuf Metrol* 5, 39–49 (2022). <https://doi.org/10.1007/s41871-021-00109-3>

Barron, C., O'Toole, S. & Zerulla, D. **Fabrication of Nanoscale Active Plasmonic Elements Using Atomic Force Microscope Tip-Based Nanomachining.** *Nanomanuf Metrol* 5, 50–59 (2022). <https://doi.org/10.1007/s41871-021-00121-7>

Black, N., Edwards, D., Browne, N. *et al.* **Deterministic Dual Control of Phase Competition in Strained BiFeO₃: A Multiparametric Structural Lithography Approach.** *Nanomanuf Metrol* 5, 60–66 (2022). <https://doi.org/10.1007/s41871-021-00123-5>

Ji, F., Yao, Y., Xin, T. *et al.* **A Comprehensive FIB Lift-out Sample Preparation Method for Scanning Probe Microscopy.** *Nanomanuf Metrol* 5, 67–79 (2022).
<https://doi.org/10.1007/s41871-021-00107-5>

Misumi, I., Kizu, R., Itoh, H. *et al.* **Research Activities of Nanodimensional Standards Using Atomic Force Microscopes, Transmission Electron Microscope, and Scanning Electron Microscope at the National Metrology Institute of Japan.** *Nanomanuf Metrol* 5, 83–90 (2022). <https://doi.org/10.1007/s41871-021-00119-1>

Dai, G., Hahm, K., Sebastian, L. *et al.* **Comparison of EUV Photomask Metrology Between CD-AFM and TEM.** *Nanomanuf Metrol* 5, 91–100 (2022).
<https://doi.org/10.1007/s41871-022-00124-y>

Du, H. **DMPFIT: A Tool for Atomic-Scale Metrology via Nonlinear Least-Squares Fitting of Peaks in Atomic-Resolution TEM Images.** *Nanomanuf Metrol* 5, 101–111 (2022). <https://doi.org/10.1007/s41871-022-00137-7>

Shkurmanov, A., Krekeler, T. & Ritter, M. **Slice Thickness Optimization for the Focused Ion Beam-Scanning Electron Microscopy 3D Tomography of Hierarchical Nanoporous Gold.** *Nanomanuf Metrol* 5, 112–118 (2022). <https://doi.org/10.1007/s41871-022-00134-w>

Wang, F., Shi, Y., Zhang, S. *et al.* **Automatic Measurement of Silicon Lattice Spacings in High-Resolution Transmission Electron Microscopy Images Through 2D Discrete Fourier Transform and Inverse Discrete Fourier Transform.** *Nanomanuf Metrol* 5, 119–126 (2022). <https://doi.org/10.1007/s41871-022-00129-7>

Bellotti, R., Picotto, G.B. & Ribotta, L. **AFM Measurements and Tip Characterization of Nanoparticles with Different Shapes.** *Nanomanuf Metrol* 5, 127–138 (2022). <https://doi.org/10.1007/s41871-022-00125-x>

Schaude, J., Hausotte, T. **Atomic Force Microscope with an Adjustable Probe Direction and Integrated Sensing and Actuation.** *Nanomanuf Metrol* 5, 139–148 (2022). <https://doi.org/10.1007/s41871-022-00143-9>

<p>Fernández Herrero, A., Scholze, F., Dai, G. <i>et al.</i> Analysis of Line-Edge Roughness Using EUV Scatterometry. <i>Nanomanuf Metrol</i> 5, 149–158 (2022). https://doi.org/10.1007/s41871-022-00126-w</p>
<p>Yuan, Y., Yao, C., Shen, W. <i>et al.</i> Polarization Measurement Method Based on Liquid Crystal Variable Retarder (LCVR) for Atomic Thin-Film Thickness. <i>Nanomanuf Metrol</i> 5, 159–166 (2022). https://doi.org/10.1007/s41871-022-00131-z</p>
<p>Shu, T., Liu, F., Chen, S. <i>et al.</i> Origins of Ultrafast Pulse Laser-Induced Nano Straight Lines with Potential Applications in Detecting Subsurface Defects in Silicon Carbide Wafers. <i>Nanomanuf Metrol</i> 5, 167–178 (2022). https://doi.org/10.1007/s41871-022-00133-x</p>
<p>Deng, X., Tan, W., Tang, Z. <i>et al.</i> Scanning and Splicing Atom Lithography for Self-traceable Nanograting Fabrication. <i>Nanomanuf Metrol</i> 5, 179–187 (2022). https://doi.org/10.1007/s41871-022-00140-y</p>
<p>Zhang, J., Li, Y., Cao, K. <i>et al.</i> Advances in Atomic Layer Deposition. <i>Nanomanuf Metrol</i> 5, 191–208 (2022). https://doi.org/10.1007/s41871-022-00136-8</p>
<p>Fan, Z., Hu, X. & Gao, R.X. Indirect Measurement Methods for Quality and Process Control in Nanomanufacturing. <i>Nanomanuf Metrol</i> 5, 209–229 (2022). https://doi.org/10.1007/s41871-022-00148-4</p>
<p>Wu, H., Zhang, H., Geng, L. <i>et al.</i> Pure Metal Clusters with Atomic Precision for Nanomanufacturing. <i>Nanomanuf Metrol</i> 5, 230–239 (2022). https://doi.org/10.1007/s41871-022-00139-5</p>
<p>Wang, J., Fang, F. & Li, L. Cutting of Graphite at Atomic and Close-to-Atomic Scale Using Flexible Enhanced Molecular Dynamics. <i>Nanomanuf Metrol</i> 5, 240–249 (2022). https://doi.org/10.1007/s41871-022-00128-8</p>
<p>Gao, J., Luo, X., Chang, W. <i>et al.</i> Insight into Atomic-Scale Adhesion at the C–Cu Interface During the Initial Stage of Nanoindentation. <i>Nanomanuf Metrol</i> 5, 250–258 (2022). https://doi.org/10.1007/s41871-022-00149-3</p>
<p>Kumar, M., Das, M. & Yu, N. Surface Roughness Simulation During Rotational–Magnetorheological Finishing of Poppet Valve Profiles. <i>Nanomanuf Metrol</i> 5, 259–273 (2022). https://doi.org/10.1007/s41871-022-00144-8</p>
<p>Nakajima, A., Omiya, M. & Yan, J. Generation of micro/nano hybrid surface structures on copper by femtosecond pulsed laser irradiation. <i>Nanomanuf Metrol</i> 5, 274–282 (2022). https://doi.org/10.1007/s41871-022-00135-9</p>
<p>Yi, R., Zhan, Z. & Deng, H. Isotropic Tuning of Electrochemical Etching for the Nanometric Finishing of Metals. <i>Nanomanuf Metrol</i> 5, 283–296 (2022). https://doi.org/10.1007/s41871-022-00151-9</p>
<p>Glynos, E., Chremos, A., Camp, P.J. <i>et al.</i> Surface Nanopatterning Using the Self-Assembly of Linear Polymers on Surfaces after Solvent Evaporation. <i>Nanomanuf Metrol</i> 5, 297–309 (2022). https://doi.org/10.1007/s41871-022-00152-8</p>
<p>Valentino, T., Radel, T. Identification of Characteristic Values in Impulse-Based Processes Using Small Specimens. <i>Nanomanuf Metrol</i> 5, 310–323 (2022). https://doi.org/10.1007/s41871-022-00142-w</p>
<p>McCormack, M., Fang, F. & Zhang, J. Numerical Analysis of Microchannels Designed for Heat Sinks. <i>Nanomanuf Metrol</i> (2021). https://doi.org/10.1007/s41871-021-00118-2</p>
<p>Chen, S., Yang, S., Cheung, C.F. <i>et al.</i> Suppression Strategy of Micro-waviness error in Ultra-precision Parallel Grinding. <i>Nanomanuf Metrol</i> (2022). https://doi.org/10.1007/s41871-022-00130-0</p>

Wang, C., Yuan, W., Chen, Y. et al. **Plowing-Extrusion Processes and Performance of Functional Surface Structures of Copper Current Collectors for Lithium-Ion Batteries.** *Nanomanuf Metrol* (2022). <https://doi.org/10.1007/s41871-022-00141-x>

Wang, Y., Zhou, T., Zhou, J. et al. **Precision Milling of Integrated Turbine Based on a Non-Contact On-Machine Measurement System.** *Nanomanuf Metrol* (2022). <https://doi.org/10.1007/s41871-022-00146-6>

Wang, Z., Chen, Z. & Zhang, X. **Profile Compensation for Single-Point Diamond Turning of Microlens Array.** *Nanomanuf Metrol* (2022). <https://doi.org/10.1007/s41871-022-00147-5>

Dai, G., Hu, X. **Correction of Interferometric High-Order Nonlinearity Error in Metrological Atomic Force Microscopy.** *Nanomanuf Metrol* (2022). <https://doi.org/10.1007/s41871-022-00154-6>

Gao, F., Lu, L., Mei, X. et al. **Capillary Performance of Nanoporous Aluminum Braided Wicks Prepared by Anodic Oxidation.** *Nanomanuf Metrol* (2022). <https://doi.org/10.1007/s41871-022-00138-6>
